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 Adel, M.; Ghinovker, M.; Golovanevsky, B.; Izikson, P.; Kassel, E.; Yaffe, D.; Bruckstein, A.M.; Goldenberg, R.; Rubner, Y.; Rudzsky, M.; Semiconductor Manufacturing, IEEE Transactions on , Volume: 17 , Issue: 2 , 2004
 Pages:166 - 179

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2 Novel, at-design-rule, via-to-metal overlay metrology for 193 nm lithography

 Ueno, A.; Tsujita, K.; Kurita, H.; Iwata, Y.; Ghinovker, M.; Kassel, E.; Adel, M.; Semiconductor Manufacturing, 2003 IEEE International Symposium on , 30 S. Oct. 2003
 Pages:134 - 137

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